

P27374.A05



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

*Please
LP (12/05/05)*

Applicants : Dureseti CHIDAMBARRAO, et al. Group Art Unit: 2814
Appln. No. : 10/605,108 Examiner: PHAM, Long
Filed : September 9, 2003 Confirmation No. 2107
For : METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI
ON SI/GE SUBSTRATE

AMENDMENT UNDER 37 C.F.R. 1.116

Commissioner for Patents
U.S. Patent and Trademark Office
Customer Window, Mail Stop AF
Randolph Building
401 Dulany Street
Alexandria, VA 22314
Sir:

Responsive to the Final Official Action of September 22, 2005, reconsideration and withdrawal of the rejections made therein are respectfully requested, in view of the following amendments and remarks.

Inasmuch as the Official Action sets a three-month shortened statutory period which expires December 22, 2005, this Amendment is being timely filed and no extension of time is believed necessary. However, if an extension is deemed by the Patent and Trademark Office to be necessary, the same is hereby requested and the Patent and Trademark Office is hereby authorized to charge any necessary fees in connection therewith or any fees necessary to preserve the pendency of this application to deposit account No. 09-0458.

Amendments to the claims begin on page 2; and
Remarks begin on page 5.